REMARKS

Claims 51-58 are pending in the application.

Claims 51-57 stand rejected under 35 U.S.C. § 102(e) as being anticipated by Tseng, U.S. Patent No. 5,830,802. The Examiner is reminded by direction to MPEP § 2131 that anticipation requires each and every element of a claim to be disclosed in a single prior art reference. Claims 51-57 are allowable over Tseng for at least the reason that Tseng fails to disclose every element in any of those claims.

Each of independent claims 51 and 55 recite forming a polycrystalline thin film transistor layer over a transistor gate, forming a fluorine-containing layer over the polycrystalline thin film transistor layer and transferring fluorine into the polycrystalline thin film transistor layer from the fluorine-containing layer. As indicated in Tseng, the disclosed invention is aimed at absorbing halogen atoms in a material layer to prevent halogen atoms form migrating from the material layer into underlying layers including migration through an underlying polycrystalline silicon layer 14 to reach gate oxide layer 16 (col. 2, II. 33 through col. 3, Il. 3). Tseng discloses formation of a dielectric layer 58 over a refractory silicide layer 56, and out diffusing halogen from the silicide layer into overlying dielectric layer 58 which is subsequently removed to prevent halogen diffusion into underlying gate layers in order to avoid detrimental effects of such diffusion (Fig. 2 and col. 3, II. 13-20, 30-32 and 56-60). Tseng clearly teaches away from the claims 51 and 55 recited transferring fluorine into a polycrystalline thin film transistor layer from an overlying fluorine-containing layer. Accordingly, claims 51 and 55 are not anticipated by Tseng and are allowable over this reference.

Dependent claims 52-54 and 56-57 are allowable over Tseng for at least the reason that they depend from corresponding allowable base claims 51 and 55.

Applicant acknowledges the Examiner's indication of the allowability of the subject matter of claim 58.

For the reasons discussed above, pending claims 51-58 are allowable. Accordingly, applicant respectfully requests formal allowance of claims 51-58 in the Examiner's next action.

Respectfully submitted,

Dated: 🗷

Rv.

lennifer / Taylor

Reg. Nø. 48,711